In the Claims:

Please amend the claims as follows:

1-10 (cancelled)

11. (new) A method for the preparation of doped oxide material, in which method substantially all the reactants forming the oxide material are brought into a vaporous reduced form in the gas phase and after this to react with each other in order to form oxide particles, wherein said reactants in vaporous and reduced form are mixed together as a gas flow of the reactants, which gas flow is further condensed fast in such a manner that substantially all the components of the reactants reach a supersaturated state in said gas flow substantially simultaneously by forming oxide particles in such a manner that there is no time to reach a chemical phase equilibrium.

12. (new) The method according to claim 11, wherein said oxide material is doped glass material, which is formed of the base materials and dopants of glass material by bringing these to react with each other in the gas phase in a vaporous reduced form and to condensate further into glass particles.

13. (new) The method according to claim 11, wherein the fast condensation of reactants into oxide particles is achieved by fast oxidation of reactants.

14. (new) The method according to claim 13, wherein said fast oxidation and condensation of reactants is achieved by directing one or more jets of oxidative gases to the gas flow of the reactants.

15. (new) The method according to claim 14, wherein the jets are formed of oxygen and/or carbon dioxide.

16. (new) The method according to claim 14, wherein said one or more jets of oxidative gases are directed to the gas flow in a manner causing strong turbulence and mixing.

17. (new) The method according to claim 14, wherein the formation of oxide particles is intensified by directing said one or more jets of oxidative gases to the gas flow of reactants as colder than said gas flow.

18. (new) The method according to claim 11, wherein the fast condensation of reactants into oxide particles is achieved and/or it is intensified by expanding the gas flow of reactants adiabatically.

19. (new) The method according to claim 18, wherein the gas flow of reactants is directed through the Lavall nozzle.

20. (new) The method according to claim 12, wherein said oxide material is glass material, as whose base material is used inorganic or organic compound of silicon or germanium.

21. (new) The method according to claim 20, wherein the compound of silicon is silicon tetrachloride, or TEOS (tetraethylortosilicate), and the compound of germanium is germanium tetrachloride, or GEOS (tetraethoxygermanium).

22. (new) The method according to the claim 11, wherein said oxide material is glass material, as whose dopant is used erbium, neodymium, other rare earth metal, aluminium, phosphorus, borium and/or fluorine.